Anjana Devi

List of Publications by Year
in descending order

217 papers	5,108 citations	76294 40 h-index	149623 56 g-index
227 all docs	227 docs citations	227 times ranked	5970 citing authors

#	Article	IF	Citations
1	F-Doped Co₃O₄ Photocatalysts for Sustainable H₂ Generation from Water/Ethanol. Journal of the American Chemical Society, 2011, 133, 19362-19365.	6.6	171
2	1D ZnO nano-assemblies by Plasma-CVD as chemical sensors for flammable and toxic gases. Sensors and Actuators B: Chemical, 2010, 149, 1-7.	4.0	169
3	Co₃O₄/ZnO Nanocomposites: From Plasma Synthesis to Gas Sensing Applications. ACS Applied Materials & Interfaces, 2012, 4, 928-934.	4.0	141
4	â€˜Old Chemistriesâ€™ for new applications: Perspectives for development of precursors for MOCVD and ALD applications. Coordination Chemistry Reviews, 2013, 257, 3332-3384.	9.5	137
5	Fabrication of heterostructured p-CuO/n-SnO2 core-shell nanowires for enhanced sensitive and selective formaldehyde detection. Sensors and Actuators B: Chemical, 2019, 290, 233-241.	4.0	106
6	Hafnium oxide thin film grown by ALD: An XPS study. Surface Science Spectra, 2007, 14, 34-40.	0.3	102
7	Urchin-like ZnO nanorod arrays for gas sensing applications. CrystEngComm, 2010, 12, 3419.	1.3	90
8	Highly Oriented ZnO Nanorod Arrays by a Novel Plasma Chemical Vapor Deposition Process. Crystal Growth and Design, 2010, 10, 2011-2018.	1.4	89
9	Plasma-assisted synthesis of Ag/ZnO nanocomposites: First example of photo-induced H2 production and sensing. International Journal of Hydrogen Energy, 2011, 36, 15527-15537.	3.8	79
10	Growth and Crystallization of TiO₂Thin Films by Atomic Layer Deposition Using a Novel Amido Guanidinate Titanium Source and Tetrakis-dimethylamido-titanium. Chemistry of Materials, 2013, 25, 2934-2943.	3.2	75
11	A Study of Bisazido(dimethylamino-propyl)gallium as a Precursor for the OMVPE of Gallium Nitride Thin Films in a Cold-Wall Reactor System under Reduced Pressure. Chemical Vapor Deposition, 2000, 6, 245-252.	1.4	69
12	Review Article: Recommended reading list of early publications on atomic layer depositionâ€"Outcome of the â€œVirtual Project on the History of ALDâ€ Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, .	0.9	65
13	Î²-Fe₂O₃nanomaterials from an iron(<scp>ii</scp>) diketonate-diamine complex: a study from molecular precursor to growth process. Dalton Transactions, 2012, 41, 149-155.	1.6	63
14	A Study on the Metal Organic CVD of Pure Copper Films from Low Cost Copper(II) Dialkylamino-2-propoxides: Tuning the Thermal Properties of the Precursor by Small Variations of the Ligand. Chemical Vapor Deposition, 2003, 9, 149-156.	1.4	60
15	Plasma enhanced-CVD of undoped and fluorine-doped Co3O4 nanosystems for novel gas sensors. Sensors and Actuators B: Chemical, 2011, 160, 79-86.	4.0	56
16	Low temperature growth of gallium oxide thin films <i>via</i> plasma enhanced atomic layer deposition. Dalton Transactions, 2017, 46, 16551-16561.	1.6	56
17	Synthesis, Characterization, and Thermal Properties of Homoleptic Rare-Earth Guanidinates: Promising Precursors for MOCVD and ALD of Rare-Earth Oxide Thin Films. Inorganic Chemistry, 2008, 47, 11405-11416.	1.9	55
18	CuO/ZnO Nanocomposite Gas Sensors Developed by a Plasmaâ€Assisted Route. ChemPhysChem, 2012, 13, 2342-2348.	1.0	55

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19	Investigations on InN whiskers grown by chemical vapour deposition. Journal of Crystal Growth, 2001, 231, 68-74.	0.7	54
20	Synthesis of nano-scale TiO2 particles by a nonhydrolytic approachElectronic supplementary information (ESI) available: TG analysis of the precursors; particle size distribution analysis of TiO2 nanocrystals dispersed in toluene; XRD analysis of TiO2 nanocrystals with and without glass substrate background. See http://www.rsc.org/suppdata/jm/b2/b202767d/. Journal of Materials Chemistry, 2002, 12, 1625-1627.	6.7	52
21	Direct Growth of MoS₂ and WS₂ Layers by Metal Organic Chemical Vapor Deposition. Advanced Materials Interfaces, 2018, 5, 1800140.	1.9	52
22	Strongly oriented thin films of Co3O4 deposited on single-crystal MgO(100) by low-pressure, low-temperature MOCVD. Journal of Crystal Growth, 2002, 240, 157-163.	0.7	49
23	Guanidinate-Stabilized Monomeric Hafnium Amide Complexes as Promising Precursors for MOCVD of HfO2. Inorganic Chemistry, 2006, 45, 11008-11018.	1.9	49
24	Ag/ZnO nanomaterials as high performance sensors for flammable and toxic gases. Nanotechnology, 2012, 23, 025502.	1.3	48
25	Atomic Layer Deposition of Gd₂O₃ and Dy₂O₃: A Study of the ALD Characteristics and Structural and Electrical Properties. Chemistry of Materials, 2012, 24, 651-658.	3.2	47
26	Low Temperature Stabilization of Nanoscale Epitaxial Spinel Ferrite Thin Films by Atomic Layer Deposition. Advanced Functional Materials, 2014, 24, 5368-5374.	7.8	47
27	Hierarchical highly ordered SnO2 nanobowl branched ZnO nanowires for ultrasensitive and selective hydrogen sulfide gas sensing. Microsystems and Nanoengineering, 2020, 6, 30.	3.4	47
28	Stabilization of Amide-Based Complexes of Niobium and Tantalum Using Malonates as Chelating Ligands: Precursor Chemistry and Thin Film Deposition. Chemistry of Materials, 2007, 19, 6077-6087.	3.2	45
29	Homoleptic Gadolinium Guanidinate: A Single Source Precursor for Metalâ€“Organic Chemical Vapor Deposition of Gadolinium Nitride Thin Films. Journal of the American Chemical Society, 2009, 131, 17062-17063.	6.6	45
30	A Cobalt(II) Hexafluoroacetylacetonate Ethylenediamine Complex As a CVD Molecular Source of Cobalt Oxide Nanostructures. Inorganic Chemistry, 2009, 48, 82-89.	1.9	45
31	Atomic layer deposition of functional multicomponent oxides. APL Materials, 2019, 7, .	2.2	45
32	An integrated experimental and theoretical investigation on Cu(hfa)2Â·TMEDA: structure, bonding and reactivity. Physical Chemistry Chemical Physics, 2009, 11, 5998.	1.3	43
33	Growth of Crystalline Gd2O3 Thin Films with a High-Quality Interface on Si(100) by Low-Temperature H2O-Assisted Atomic Layer Deposition. Journal of the American Chemical Society, 2010, 132, 36-37.	6.6	43
34	Low-Temperature Atomic Layer Deposition of Cobalt Oxide as an Effective Catalyst for Photoelectrochemical Water-Splitting Devices. Chemistry of Materials, 2017, 29, 5796-5805.	3.2	43
35	Evaluation of Homoleptic Guanidinate and Amidinate Complexes of Gadolinium and Dysprosium for MOCVD of Rare-Earth Nitride Thin Films. Chemistry of Materials, 2011, 23, 1430-1440.	3.2	42
36	Nanostructured Dy2O3 films: An XPS Investigation. Surface Science Spectra, 2007, 14, 52-59.	0.3	41

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37	Lanthanide Oxide Thin Films by Metalorganic Chemical Vapor Deposition Employing Volatile Guanidinate Precursors. Chemistry of Materials, 2009, 21, 5443-5455.	3.2	41
38	Electrical and optical properties of TiO₂ thin films prepared by plasmaâ€enhanced atomic layer deposition. Physica Status Solidi (A) Applications and Materials Science, 2014, 211, 416-424.	0.8	41
39	Photoactive Zinc Ferrites Fabricated via Conventional CVD Approach. ACS Sustainable Chemistry and Engineering, 2017, 5, 2917-2926.	3.2	41
40	ZnO Nanorod Arrays by Plasmaâ€Enhanced CVD for Lightâ€Activated Functional Applications. ChemPhysChem, 2010, 11, 2337-2340.	1.0	40
41	Strain-induced phase transitions in epitaxial NaNbO₃thin films grown by metalâ€“organic chemical vapour deposition. Journal of Applied Crystallography, 2012, 45, 1015-1023.	1.9	40
42	Sc2O3, Er2O3, and Y2O3 thin films by MOCVD from volatile guanidinate class of rare-earth precursors. Dalton Transactions, 2012, 41, 13936.	1.6	40
43	Synthesis and structure of mixed isopropoxideâ€“Î²-ketoester and Î²-ketoamide zirconium complexes: Potential precursors for MOCVD of ZrO2. Journal of Materials Chemistry, 2003, 13, 2177-2184.	6.7	39
44	Water assisted atomic layer deposition of yttrium oxide using tris(<i>N</i>,<i>N</i>â€²-diisopropyl-2-dimethylamido-guanidinato) yttrium(<scp>iii</scp>): process development, film characterization and functional properties. RSC Advances, 2018, 8, 4987-4994.	1.7	38
45	Volatile, Monomeric, and Fluorineâ€Free Precursors for the Metal Organic Chemical Vapor Deposition of Zinc Oxide. European Journal of Inorganic Chemistry, 2010, 2010, 1366-1372.	1.0	37
46	PEALD of SiO₂ and Al₂O₃ Thin Films on Polypropylene: Investigations of the Film Growth at the Interface, Stress, and Gas Barrier Properties of Dyads. ACS Applied Materials & Interfaces, 2018, 10, 7422-7434.	4.0	37
47	Design, synthesis and antimicrobial evaluation of novel 1-benzyl 2-butyl-4-chloroimidazole embodied 4-azafluorenones via molecular hybridization approach. Bioorganic and Medicinal Chemistry Letters, 2012, 22, 7475-7480.	1.0	35
48	Manganese(II) Molecular Sources for Plasma-Assisted CVD of Mn Oxides and Fluorides: From Precursors to Growth Process. Journal of Physical Chemistry C, 2018, 122, 1367-1375.	1.5	34
49	Molecular Engineering of Mn^{II} Diamine Diketonate Precursors for the Vapor Deposition of Manganese Oxide Nanostructures. Chemistry - A European Journal, 2017, 23, 17954-17963.	1.7	33
50	Low-Temperature Plasma-Enhanced Atomic Layer Deposition of Tin(IV) Oxide from a Functionalized Alkyl Precursor: Fabrication and Evaluation of SnO₂-Based Thin-Film Transistor Devices. ACS Applied Materials & Interfaces, 2019, 11, 3169-3180.	4.0	33
51	Gd2O3 Nanostructured Thin Films Analyzed by XPS. Surface Science Spectra, 2007, 14, 60-67.	0.3	32
52	Intrinsic Nitrogenâ€doped CVDâ€grown TiO₂ Thin Films from Allâ€Nâ€coordinated Ti Precursors for Photoelectrochemical Applications. Chemical Vapor Deposition, 2013, 19, 45-52.	1.4	32
53	Recent Advances Using Guanidinate Ligands for Chemical Vapour Deposition (CVD) and Atomic Layer Deposition (ALD) Applications. Australian Journal of Chemistry, 2014, 67, 989.	0.5	32
54	Fabrication of ZrO₂ and ZrN Films by Metalorganic Chemical Vapor Deposition Employing New Zr Precursors. Crystal Growth and Design, 2012, 12, 5079-5089.	1.4	31

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55	Indium-tris-guanidinates: a promising class of precursors for water assisted atomic layer deposition of In₂O₃thin films. Dalton Transactions, 2014, 43, 937-940.	1.6	31
56	MOCVD of TiO2thin films and studies on the nature of molecular mechanisms involved in the decomposition of [Ti(OPri)2(tbaoac)2]. Journal of Materials Chemistry, 2004, 14, 3231-3238.	6.7	30
57	All-Nitrogen Coordinated Amidinato/Imido Complexes of Molybdenum and Tungsten: Syntheses and Characterization. Inorganic Chemistry, 2010, 49, 8487-8494.	1.9	30
58	Atomic Layer Deposition of Nickel on ZnO Nanowire Arrays for High-Performance Supercapacitors. ACS Applied Materials & Interfaces, 2018, 10, 468-476.	4.0	30
59	A novel Cu(II) chemical vapor deposition precursor: Synthesis, characterization, and chemical vapor deposition. Journal of Materials Research, 1998, 13, 687-692.	1.2	29
60	Novel Gallium Complexes with Malonic Diester Anions as Molecular Precursors for the MOCVD of Ga₂O₃ Thin Films. European Journal of Inorganic Chemistry, 2009, 2009, 1110-1117.	1.0	28
61	Heteroleptic Guanidinateâ€•and Amidinateâ€Based Complexes of Hafnium as New Precursors for MOCVD of HfO₂. European Journal of Inorganic Chemistry, 2010, 2010, 1679-01688.	1.0	28
62	Nanostructured Fe₂O₃ Processing via Waterâ€Assisted ALD and Lowâ€Temperature CVD from a Versatile Iron Ketoiminate Precursor. Advanced Materials Interfaces, 2017, 4, 1700155.	1.9	28
63	MOCVD of gallium nitride nanostructures using (N3)2Ga{(CH2)3NR2}, R = Me, Et, as a single molecule precursor: morphology control and materials characterization. Journal of Materials Chemistry, 2003, 13, 1438.	6.7	27
64	Mononuclear precursor for MOCVD of HfO2 thin filmsElectronic supplementary information (ESI) available: TG/DTA, and isothermal studies, RBS and AFM data of HfO2 film. See http://www.rsc.org/suppdata/cc/b4/b405015k/. Chemical Communications, 2004, , 1610.	2.2	27
65	MOCVD of ZnO Films from <i>Bis</i>(Ketoiminato)Zn(II) Precursors: Structure, Morphology and Optical Properties. Chemical Vapor Deposition, 2011, 17, 155-161.	1.4	27
66	Plasma Processing of Nanomaterials: Emerging Technologies for Sensing and Energy Applications. Journal of Nanoscience and Nanotechnology, 2011, 11, 8206-8213.	0.9	27
67	Low-Temperature Atomic Layer Deposition of Low-Resistivity Copper Thin Films Using Cu(dmap)₂ and Tertiary Butyl Hydrazine. Chemistry of Materials, 2017, 29, 6502-6510.	3.2	27
68	Strongly oriented Co3O4 thin films on MgO(100) and MgAl2O4(100) substrates by PE-CVD. CrystEngComm, 2011, 13, 3670.	1.3	26
69	Surfactant-Induced Nonhydrolytic Synthesis of Phase-Pure ZrO₂ Nanoparticles from Metalâ€“Organic and Oxocluster Precursors. Chemistry of Materials, 2012, 24, 4274-4282.	3.2	26
70	Atomic Layer Deposition of Molybdenum and Tungsten Oxide Thin Films Using Heteroleptic Imido-Amidinato Precursors: Process Development, Film Characterization, and Gas Sensing Properties. Chemistry of Materials, 2018, 30, 8690-8701.	3.2	26
71	Novel insight into the alignment and structural ordering of supported ZnO nanorods. Chemical Physics Letters, 2010, 500, 287-290.	1.2	25
72	CVD-grown copper tungstate thin films for solar water splitting. Journal of Materials Chemistry A, 2018, 6, 10206-10216.	5.2	25

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73	Mononuclear MixedÎ²-Ketoester-alkoxide Compound of Titanium as a Promising Precursor for Low-Temperature MOCVD of TiO2 Thin Films. Chemical Vapor Deposition, 2003, 9, 295-298.	1.4	24
74	Liquid-Injection MOCVD of ZrO2 Thin Films using Zirconium Bis(diethlyamido)-bis(di-tert-butylmalonato) as a Novel Precursor. Chemical Vapor Deposition, 2006, 12, 295-300.	1.4	24
75	Thin Films of HfO[sub 2] for High-k Gate Oxide Applications from Engineered Alkoxide- and Amide-Based MOCVD Precursors. Journal of the Electrochemical Society, 2007, 154, G77.	1.3	24
76	Synthesis and characterisation of zirconiumâ€“amido guanidinato complex: a potential precursor for ZrO2thin films. Dalton Transactions, 2007, , 1671-1676.	1.6	24
77	Homoleptic Gadolinium Amidinates as Precursors for MOCVD of Oriented Gadolinium Nitride (GdN) Thin Films. Inorganic Chemistry, 2013, 52, 286-296.	1.9	24
78	An efficient PE-ALD process for TiO₂ thin films employing a new Ti-precursor. Journal of Materials Chemistry C, 2016, 4, 1057-1065.	2.7	24
79	Transition metal nitride thin films grown by MOCVD using amidinato based complexes [M(NtBu)2{(iPrN)2CMe}2] (M=Mo, W) as precursors. Surface and Coatings Technology, 2013, 230, 130-136.	2.2	23
80	[Zr(NEtMe)₂(guan-NEtMe)₂] as a Novel Atomic Layer Deposition Precursor: ZrO₂ Film Growth and Mechanistic Studies. Chemistry of Materials, 2013, 25, 3088-3095.	3.2	23
81	New amidinate complexes of indium(<scp>iii</scp>): promising CVD precursors for transparent and conductive In₂O₃ thin films. Dalton Transactions, 2017, 46, 10220-10231.	1.6	23
82	Monomeric malonate precursors for the MOCVD of HfO₂and ZrO₂thin films. Dalton Transactions, 2009, , 654-663.	1.6	22
83	Atomic Layer Deposition of HfO₂ Thin Films Employing a Heteroleptic Hafnium Precursor. Chemical Vapor Deposition, 2012, 18, 27-35.	1.4	22
84	An Nâ€Heterocyclic Carbene Based Silver Precursor for Plasmaâ€Enhanced Spatial Atomic Layer Deposition of Silver Thin Films at Atmospheric Pressure. Angewandte Chemie - International Edition, 2018, 57, 16224-16227.	7.2	22
85	Thin Films of ZrO2 for High-k Applications Employing Engineered Alkoxide- and Amide-Based MOCVD Precursors. Chemical Vapor Deposition, 2007, 13, 98-104.	1.4	21
86	Malonate complexes of dysprosium: synthesis, characterization and application for LI-MOCVD of dysprosium containing thin films. Dalton Transactions, 2011, 40, 62-78.	1.6	21
87	PEALD of HfO₂ Thin Films: Precursor Tuning and a New Near-Ambient-Pressure XPS Approach to in Situ Examination of Thin-Film Surfaces Exposed to Reactive Gases. ACS Applied Materials & Interfaces, 2019, 11, 28407-28422.	4.0	21
88	Investigation of niobium nitride and oxy-nitride films grown by MOCVD. Surface and Coatings Technology, 2009, 204, 404-409.	2.2	20
89	Hafnium carbamates and ureates: new class of precursors for low-temperature growth of HfO2 thin films. Chemical Communications, 2009, , 1978.	2.2	20
90	Precursor chemistry for TiO2: titanium complexes with a mixed nitrogen/oxygen ligand sphere. Dalton Transactions, 2006, , 3485.	1.6	19

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91	Mixed amideâ€“malonate compound of hafnium as a novel monomeric precursor for MOCVD of HfO2thin films. Journal of Materials Chemistry, 2006, 16, 437-440.	6.7	18
92	MOCVD of ZrO2 and HfO2 Thin Films from Modified Monomeric Precursors. Chemical Vapor Deposition, 2006, 12, 172-180.	1.4	18
93	LI-MOCVD of HfO2 thin films using engineered amide based Hf precursors. Surface and Coatings Technology, 2007, 201, 9109-9116.	2.2	18
94	Atomic layer deposition of Er2O3 thin films from Er tris-guanidinate and water: process optimization, film analysis and electrical properties. Journal of Materials Chemistry C, 2013, 1, 3939.	2.7	18
95	Designing Stability into Thermally Reactive Plumbylenes. Inorganic Chemistry, 2018, 57, 8218-8226.	1.9	18
96	Synthesis of rare-earth metal and rare-earth metal-fluoride nanoparticles in ionic liquids and propylene carbonate. Beilstein Journal of Nanotechnology, 2018, 9, 1881-1894.	1.5	18
97	Metal-Organic CVD of Conductive and Crystalline Hafnium Nitride Films. Chemical Vapor Deposition, 2005, 11, 294-297.	1.4	17
98	The Synthesis of ZrO2/SiO2 Nanocomposites by the Two-Step CVD of a Volatile Halogen-Free Zr Alkoxide in a Fluidized-Bed Reactor. Chemical Vapor Deposition, 2007, 13, 37-41.	1.4	17
99	Systematic molecular engineering of Zn-ketoiminates for application as precursors in atomic layer depositions of zinc oxide. Dalton Transactions, 2016, 45, 19012-19023.	1.6	17
100	Synthesis and evaluation of new copper ketoiminate precursors for a facile and additive-free solution-based approach to nanoscale copper oxide thin films. Dalton Transactions, 2017, 46, 2670-2679.	1.6	17
101	Atomic/molecular layer deposition of hybrid inorganicâ€“organic thin films from erbium guanidinate precursor. Journal of Materials Science, 2017, 52, 6216-6224.	1.7	17
102	Bendable Polycrystalline and Magnetic CoFe₂O₄ Membranes by Chemical Methods. ACS Applied Materials & Interfaces, 2022, 14, 12845-12854.	4.0	17
103	Highly sensitive and stable MEMS acetone sensors based on well-designed Î±-Fe2O3/C mesoporous nanorods. Journal of Colloid and Interface Science, 2022, 622, 156-168.	5.0	17
104	Cobalt Metal ALD: Understanding the Mechanism and Role of Zinc Alkyl Precursors as Reductants for Low-Resistivity Co Thin Films. Chemistry of Materials, 2021, 33, 5045-5057.	3.2	16
105	Direct liquid injection chemical vapor deposition of ZrO2 films from a heteroleptic Zr precursor: interplay between film characteristics and corrosion protection of stainless steel. Journal of Materials Research and Technology, 2021, 13, 1599-1614.	2.6	16
106	Metalorganic chemical vapor deposition of Cu films from bis(t-butyl-3-oxo-butanoato)copper(II): thermodynamic investigation and experimental verification. Surface and Coatings Technology, 2002, 150, 205-211.	2.2	15
107	Spectroscopic investigation of wheat grains (Triticum aestivum) infected by wheat seed gall nematodes (Anguina tritici). Biocatalysis and Agricultural Biotechnology, 2017, 9, 58-66.	1.5	15
108	Unearthing [3â€(Dimethylamino)propyl]aluminium(III) Complexes as Novel Atomic Layer Deposition (ALD) Precursors for Al₂O₃: Synthesis, Characterization and ALD Process Development. Chemistry - A European Journal, 2017, 23, 10768-10772.	1.7	15

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109	Atomic layer deposition of dielectric Y₂O₃ thin films from a homoleptic yttrium formamidinate precursor and water. RSC Advances, 2021, 11, 2565-2574.	1.7	15
110	Precursor chemistry of Group III nitrides. Journal of Organometallic Chemistry, 2000, 602, 29-36.	0.8	14
111	Materials Chemistry of Group 13 Nitrides. , 0, , 49-80.		14
112	Rational Development of Cobalt Î²-Ketoiminate Complexes: Alternative Precursors for Vapor-Phase Deposition of Spinel Cobalt Oxide Photoelectrodes. Inorganic Chemistry, 2018, 57, 5133-5144.	1.9	14
113	Atomic/molecular layer deposition of Cuâ€"organic thin films. Dalton Transactions, 2018, 47, 15791-15800.	1.6	14
114	Tuning Coordination Geometry of Nickel Ketoiminates and Its Influence on Thermal Characteristics for Chemical Vapor Deposition of Nanostructured NiO Electrocatalysts. Inorganic Chemistry, 2020, 59, 10059-10070.	1.9	14
115	Molecular Permeation in Freestanding Bilayer Silica. Nano Letters, 2022, 22, 1287-1293.	4.5	14
116	An Efficient Chemical Solution Deposition Method for Epitaxial Gallium Nitride Layers Using a Single-Molecule Precursor. Advanced Functional Materials, 2001, 11, 224-228.	7.8	13
117	Growth and Characterization of Tiâ€Taâ€O Thin Films on Si Substrates by Liquid Injection MOCVD for Highâ€<i>k</i> Applications from Modified Titanium and Tantalum Precursors. Chemical Vapor Deposition, 2010, 16, 157-165.	1.4	13
118	Effects of Post Annealing Treatments on the Interfacial Chemical Properties and Band Alignment of AlN/Si Structure Prepared by Atomic Layer Deposition. Nanoscale Research Letters, 2017, 12, 102.	3.1	13
119	Fabrication of zinc-dicarboxylate- and zinc-pyrazolate-carboxylate-framework thin films through vapourâ€"solid deposition. Dalton Transactions, 2018, 47, 14179-14183.	1.6	13
120	Up-converting ALD/MLD thin films with Yb3+, Er3+ in amorphous organic framework. Journal of Luminescence, 2019, 213, 310-315.	1.5	13
121	How water flips at charged titanium dioxide: an SFG-study on the waterâ€"TiO₂ interface. Physical Chemistry Chemical Physics, 2019, 21, 8956-8964.	1.3	13
122	Atomic scale growth of GdFeO3 perovskite thin films. Thin Solid Films, 2020, 698, 137848.	0.8	13
123	From Precursor Chemistry to Gas Sensors: Plasmaâ€Enhanced Atomic Layer Deposition Process Engineering for Zinc Oxide Layers from a Nonpyrophoric Zinc Precursor for Gas Barrier and Sensor Applications. Small, 2020, 16, e1907506.	5.2	13
124	Facile Chemical Route to Prepare Water Soluble Epitaxial Sr₃Al₂O₆ Sacrificial Layers for Freeâ€Standing Oxides. Advanced Materials Interfaces, 2021, 8, 2001643.	1.9	13
125	Tailoring iron(<scp>III</scp>) oxide nanomorphology by chemical vapor deposition: Growth and characterization. Physica Status Solidi (A) Applications and Materials Science, 2014, 211, 316-322.	0.8	12
126	A combinatorial approach to enhance barrier properties of thin films on polymers: Seeding and capping of PECVD thin films by PEALD. Plasma Processes and Polymers, 2018, 15, 1700209.	1.6	12

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127	A carbene stabilized precursor for the spatial atomic layer deposition of copper thin films. Chemical Communications, 2020, 56, 13752-13755.	2.2	12
128	A new metalorganic chemical vapor deposition process for MoS₂ with a 1,4-diazabutadienyl stabilized molybdenum precursor and elemental sulfur. Dalton Transactions, 2020, 49, 13462-13474.	1.6	12
129	Study on Structural and Thermal Characteristics of Heteroleptic Yttrium Complexes as Potential Precursors for Vapor Phase Deposition. European Journal of Inorganic Chemistry, 2020, 2020, 3587-3596.	1.0	12
130	Low-Temperature Structure of Two Copper-Based Precursors for MOCVD: Aquabis(tert-butyl) Tj ETQq0 0 0 rgBT /Overlock 10 Tf 50 627 Crystal Structure Communications, 1996, 52, 891-894.	0.4	11
131	Growth of epitaxial sodium-bismuth-titanate films by metal-organic chemical vapor phase deposition. Thin Solid Films, 2011, 520, 239-244.	0.8	11
132	Influence of process parameters on the crystallinity, morphology and composition of tungsten oxide-based thin films grown by metalorganic chemical vapor deposition. Thin Solid Films, 2012, 522, 11-16.	0.8	11
133	Surface Decoration of <i>Ïµ</i>â€Fe₂O₃ Nanorods by CuO Via a Twoâ€Step CVD/Sputtering Approach**. Chemical Vapor Deposition, 2014, 20, 313-319.	1.4	11
134	Influence of PE-CVD and PE-ALD on defect formation in permeation barrier films on PET and correlation to atomic oxygen fluence. Journal Physics D: Applied Physics, 2017, 50, 235201.	1.3	11
135	Comparative Study of Photocarrier Dynamics in CVD-deposited CuWO₄, CuO, and WO₃ Thin Films for Photoelectrocatalysis. Zeitschrift Fur Physikalische Chemie, 2020, 234, 699-717.	1.4	11
136	A Rare Lowâ€Spin Co IV Bis(Î²â€silyldiamide) with High Thermal Stability: Steric Enforcement of a Doublet Configuration. Angewandte Chemie - International Edition, 2020, 59, 14138-14142.	7.2	11
137	Rational Development of Guanidinate and Amidinate Based Cerium and Ytterbium Complexes as Atomic Layer Deposition Precursors: Synthesis, Modeling, and Application. Chemistry - A European Journal, 2021, 27, 4913-4926.	1.7	11
138	MOCVD of aluminium oxide films using aluminium Î²-diketonates as precursors. European Physical Journal Special Topics, 2002, 12, 139-146.	0.2	10
139	Liquid injection MOCVD of TiO2 and SrTiO3 thin films from [Ti(OPri)2(tbaoac)2]: Film properties and compatibility with [Sr(thd)2]. Surface and Coatings Technology, 2007, 201, 9135-9140.	2.2	10
140	Innovative M(Hfa)2â€¢TMEDA (M=Cu, Co) Precursors for the CVD of Copper-Cobalt Oxides: an Integrated Theoretical and Experimental Approach. ECS Transactions, 2009, 25, 549-556.	0.3	10
141	Chemical vapour deposition of thin copper films using a new metalorganic precursor. Journal of Materials Science Letters, 1996, 15, 573-575.	0.5	9
142	Title is missing!. Journal of Materials Science Letters, 1998, 17, 367-369.	0.5	9
143	Morphology controlled growth of arrays of GaN nanopillars and randomly distributed GaN nanowires on sapphire using (N3)2Ga[(CH2)3NMe2] as a single molecule precursorElectronic supplementary information (ESI) available: characterisation data. See http://www.rsc.org/suppdata/cc/b2/b201858f/. Chemical Communications, 2002, , 998-999.	2.2	9
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